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Sheet 1 of 1

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INFORMATION DISCLOSURE STATEMENT
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Filing Date: July 29, 1997

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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>JH</i>	4,113,515	09/12/1978	Kooi, E., et al.	148	1.5	03/29/76
<i>ba</i>	4,462,150	07/31/1984	Nishimura, H., et al.	29	576 B	09/16/82
<i>se</i>	4,768,072	08/30/1988	Seki, Y., et al.	357	29	10/02/86
<i>gc</i>	4,841,349	06/20/1989	Nakano, M.	357	30	10/28/87
<i>KL</i>	5,407,845	04/18/1995	Nasu, Y., et al.	437	40	10/13/93
<i>gh</i>	5,789,276	08/04/1998	Leas, J.M., et al.	438	59	12/08/95
<i>gh</i>	5,858,811	01/12/1999	Tohyama, S.	438	75	01/15/97
<i>gh</i>	6,018,166	01/25/2000	Lin, K., et al.	257	22	07/30/98
<i>gh</i>	6,034,001	03/07/2000	Shor, J.S., et al.	438	931	02/17/94
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<i>se</i>	01-115162	05/08/1989	Japan	H01L	29/78	
<i>gh</i>	0291951	11/23/1988	European	H01L	29/64	
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OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

Examiner Initial	Document
<i>JH</i>	Zirinsky, S., et al., "Electrical Resistivity of Amorphous Silicon Resistor Films", <u>Extended Abstracts of the Spring Meeting of the Electrochemical Society</u> , Washington, DC, pp. 147-149, (1971)

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Examiner *JH Ebert* Date Considered *5/19/01*

*Substitute Disclosure Statement Form (PTO-1449)

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